

IN THE SPECIFICATION:

Please replace paragraph [0031] with the following amended paragraph:

[0031] Figures 4A-4D show an embodiment in which all of the first non-carbon based layer 205 is removed during processing. Figure 4A corresponds to Figure 3C, except that the first non-carbon based layer 205 has been removed. A second non-carbon based layer 220 is then deposited on the amorphous carbon layer 204 and the exposed substrate 202, and a photoresist 222 is deposited on the second non-carbon based layer 220, as shown in Figure 4B. The photoresist 222 is patterned to include features 224, as shown in Figure 4C. The features 224 patterned in the photoresist 222 are transferred to the amorphous carbon layer 204 and the non-carbon based layer 220 to create feature 208 in the in the amorphous carbon layer 204 and the non-carbon based layer 220, and the photoresist 222 is removed, as shown in ~~[[Figure 4]]~~ Figure 4D. Figure 4D substantially corresponds to Figure 3E. The substrate 202 is then etched, as shown in Figure 3F.